

ABSTRACT OF THE DISCLOSURE

In order to realize the manufacture of a reflection type liquid crystal display in the same manufacture processes as those of a transmission type liquid crystal display, a photolithography mask capable of forming both a gate electrode 22 and a reflective layer 23, and a photolithography mask capable of forming only the gate electrode 22 are prepared, and by using either one of the masks, the reflection type liquid crystal display in which both the gate electrode 22 and the reflective layer 23 are formed on a transparent insulation substrate 21, and the transmission type liquid crystal display in which only the gate electrode 22 is formed are selectively manufactured.

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